ABSTRACT OF THE DISCLOSURE

A semiconductor device composed of: a substrate having a doped semiconductor region, a gate wiring, a lower conductor structure, an insulating layer overlying the lower structure and having at least one through opening extending to the lower conductor structure, and an upper conductor structure connected to the lower conductor structure via the through opening, wherein at least one of the conductor structures is formed of at least one layer of a metal, a metal silicide, a metal nitride, a metal carbide or a conductive oxide film, and a metal plating layer disposed on and adhering to the at least one layer.

35-5